

Self-Matched ESD Cell in CMOS Technology for 60-GHz Broadband RF Applications

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Abstract — A self-matched ESD cell library has been implemented in a commercial sub-100nm CMOS process for 60-GHz broadband RF applications. This ESD cell library has reached the 50- Ω input/output matching to reduce the design complexity for RF circuit designer and to provide suitable electrostatic discharge (ESD) protection. Experimental results of this ESD cell library have successfully verified the ESD robustness and the RF characteristics in the 60-GHz frequency band. This self-matched ESD cell library is easily to be used for ESD protection design in the 60-GHz broadband RF applications.

Index Terms — Broadband, electrostatic discharge (ESD), ESD cell, V-band, 60 GHz.

I. INTRODUCTION

With the scaling-down feature size, improving high-frequency characteristics, low power consumption, high integration capability, and low cost for mass production, the nanoscale CMOS technology has been used to implement RF circuits. However, the thinner gate oxide in nanoscale CMOS technology seriously degrades the electrostatic discharge (ESD) robustness of IC products. Therefore, on-chip ESD protection circuits must be added at all input/output ports in RF IC against ESD damages [1]. To minimize the impacts from ESD protection circuit on RF performances, the ESD protection circuit at input/output ports must be carefully designed. Several ESD protection designs have been reported for RF circuits [2], [3]. As the operating frequencies of RF circuits are increasing, on-chip ESD protection designs for RF applications are more challenging.

The frequency band of 57~64 GHz has been allocated for unlicensed usage in the next-generation wireless communications. RF circuits operating at this 60-GHz band have the benefits of excellent interference immunity, high security, multi-gigabit speed, and frequency reusable. Recently, several CMOS transceivers operating at this frequency band have been reported. Some ESD protection designs for the circuits operating at this frequency band were also presented [4], [5]. In the ESD protection design in [4], the on-chip inductor is used to

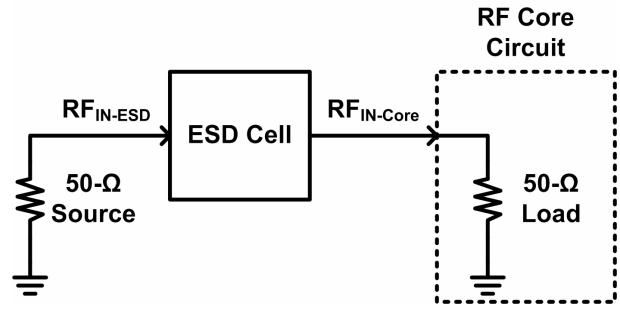


Fig. 1. Self-matched ESD cell for 60-GHz broadband RF applications.

resonate with the capacitive ESD diode to form a series LC resonator. At frequencies above the resonant frequency of the series LC resonator, the impedance becomes large, which means the signal loss from the ESD protection circuit is reduced. Hence, the series LC resonator can be used to protect the 60-GHz circuits. However, the transient voltage across the RF circuits under ESD stress is the total voltage drop across the inductor and the diode. To improve ESD robustness of the RF circuits, the transient voltage across the RF circuits under ESD stress must be reduced, especially for the circuits realized in nanoscale CMOS technology. In another ESD protection design in [5], ESD inductor is co-designed with the 60-GHz power amplifier. The ESD inductor acts part of the RF matching network. Of course, the ESD inductor has been carefully designed to provide ESD current path.

To reduce the design complexity for RF circuit designer, a self-matched ESD-protection cell library in CMOS technology for 60-GHz broadband RF applications is implemented in this work. As shown in Fig. 1, this ESD cell library has reached the 50- Ω input/output matching. Such ESD cell library has been verified in a commercial sub-100nm CMOS process to verify its ESD robustness and broadband RF performances.

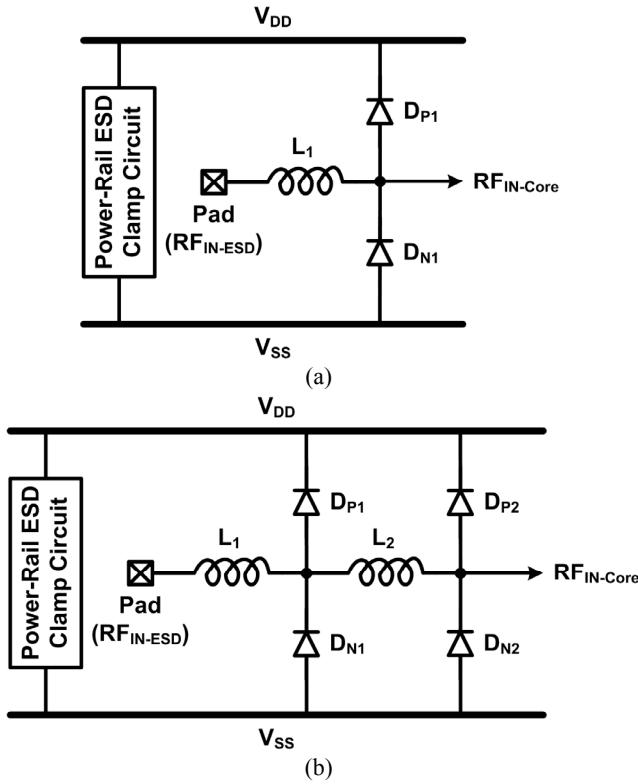


Fig. 2. Circuit diagrams of ESD cells with (a) 1-stage ESD protection and (b) 2-stage ESD protection.

II. ESD CELL DESIGN

The distributed ESD protection scheme is used to implement the ESD cells in this work to provide broadband impedance matching around 60 GHz [6], [7]. This ESD cell library provides four ESD cells with different ESD robustness, as listed in Table I. These four ESD cells are designed to sustain 0.5-, 1-, 1.5-, and 2-kV human-body-model (HBM) ESD tests, respectively. Fig. 2(a) shows the circuit diagrams of the 0.5- and 1-kV cells with 1-stage ESD protection. The 1-stage ESD protection is designed with a low-C pad, an on-chip spiral inductor, and a pair of ESD diodes. Similarly, the circuit diagrams of the 1.5- and 2-kV cells with 2-stage ESD protection are shown in Fig. 2(b). The 2-stage ESD protection is designed with a low-C pad, two on-chip spiral inductors, and two pairs of ESD diodes. Besides, the power-rail ESD clamp circuit is added in each ESD cells to provide ESD current paths between V_{DD} and V_{SS} . An RC-inverter-triggered NMOS with $\sim 2000\text{-}\mu\text{m}$ width is used as the power-rail ESD clamp circuit in this work. Since the power-rail ESD clamp circuit is placed between V_{DD} and V_{SS} , it does not contribute any parasitic effects to input/output ports. When the positive-to- V_{DD} (negative-to-

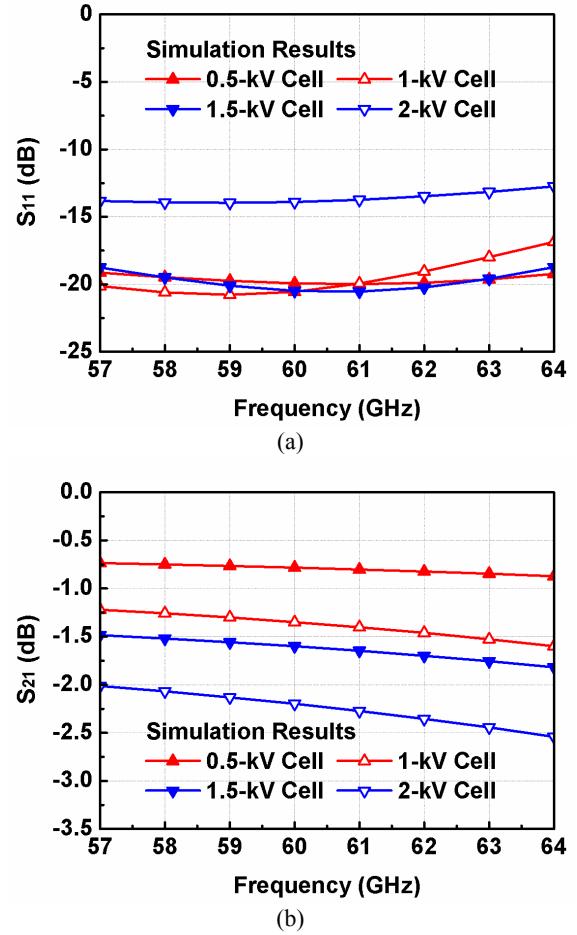


Fig. 3. Simulation results of ESD cells on (a) S_{11} , and (b) S_{21} , parameters.

V_{SS}) ESD stress occurs at the pad, the ESD current can be discharged through the diodes D_p (D_N) from the pad to V_{DD} (V_{SS}). Under positive-to- V_{DD} (negative-to- V_{DD}) ESD stress, the ESD current path consists of the diodes D_p (D_N) and the power-rail ESD clamp circuit. The ESD cells can provide the corresponding current discharging paths under all ESD stress modes.

The design parameters of the ESD cells are listed in Table I. The RF characteristics of the ESD cells are simulated by using the microwave circuit simulator ADS with layout parameters. A signal source with $50\text{-}\Omega$ impedance drives the RF_{IN-ESD} of the cell, and a $50\text{-}\Omega$ load is connected to $RF_{IN-Core}$ to simulate the RF circuit. The reflection (S_{11}) parameters are shown in Fig. 3(a). These ESD cells exhibit good input matching ($S_{11} < -12$ dB) among 57~64 GHz. The transmission (S_{21}) parameters are compared in Fig. 3(b). At 60-GHz frequency, the 0.5-, 1-, 1.5-, and 2-kV cells have about 0.8-, 1.3-, 1.6-, and 2.2-dB power loss, respectively.

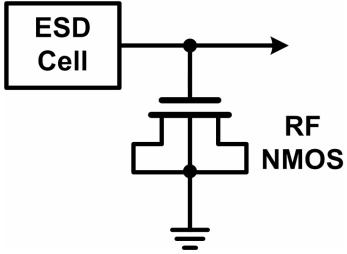


Fig. 4. RF-NMOS emulator to verify ESD protection effectiveness of the proposed ESD cell.

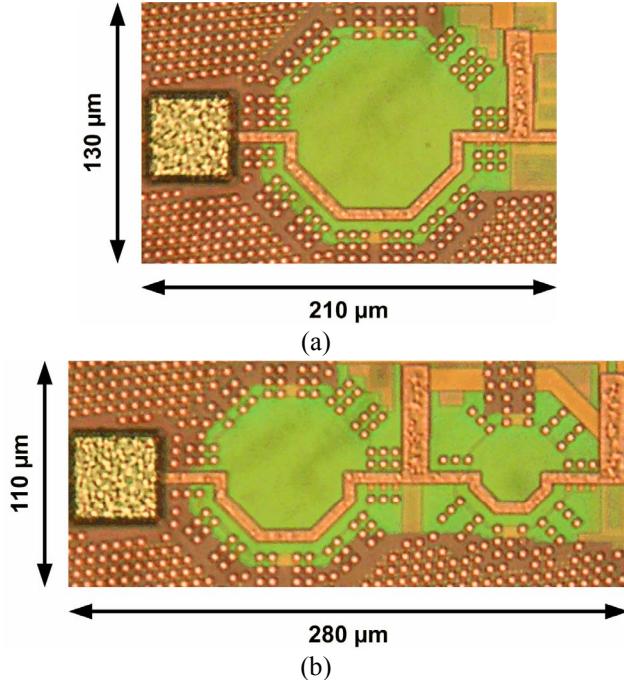


Fig. 5. Die photos of (a) 1-kV cell and (b) 2-kV cell.

One set of these test circuits are arranged with G-S-G style in layout to facilitate the on-wafer RF measurement. Besides, another set of the test circuits are implemented with the RF-NMOS emulator, as shown in Fig. 4. The ESD robustness of the ESD-protected RF circuits can be estimated by the ESD cell with the RF-NMOS emulator. All test circuits have been fabricated in a commercial sub-100nm CMOS process for RF and ESD verifications. Fig. 5 shows the die photos of the 1- and 2-kV cells.

III. EXPERIMENTAL RESULTS

A. RF Performances

The S-parameters of these four ESD cells have been measured around 60 GHz. The voltage supply of V_{DD} (V_{SS}) is 1.2 V (0 V), and the input dc bias is 0.6 V. The source and load resistances to the test circuits are kept at 50Ω .

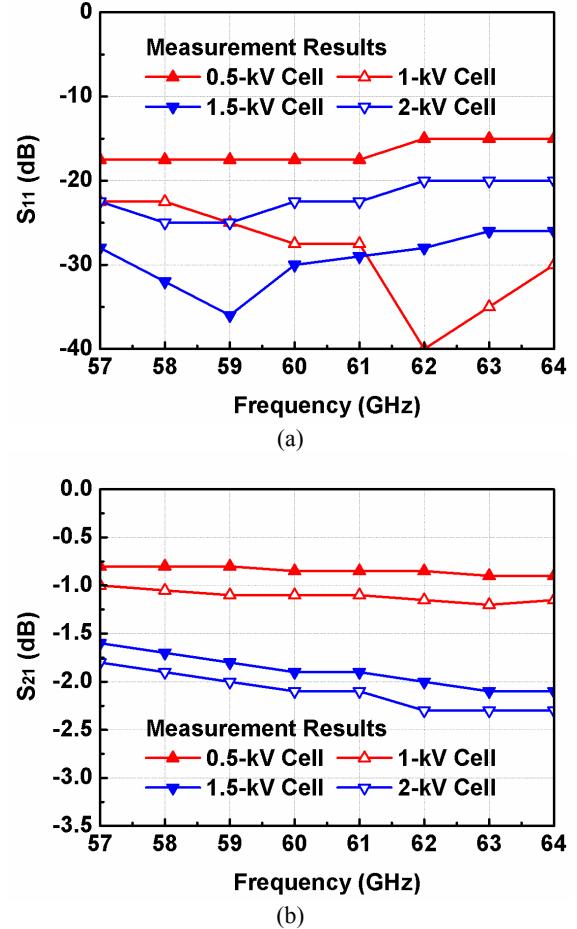


Fig. 6. Measurement results of the fabricated ESD cells on (a) S_{11} , and (b) S_{21} , parameters.

The measured S_{11} and S_{21} parameters versus frequency are shown in Figs. 6(a) and 6(b), respectively. As shown in Fig. 6(a), these ESD cells exhibit good input matching ($S_{11} < -20$ dB) among 57~64 GHz. At 60-GHz frequency, the 0.5-, 1-, 1.5-, and 2-kV cells have about 0.9-, 1.1-, 1.9-, and 2.1-dB power loss, respectively. The measurement results of the ESD cells are well matching to the simulation results. Hence, applying these ESD cells to RF circuits, the performances can be exactly simulated during the design phase of the RF circuits.

B. ESD Robustness

The HBM ESD robustness of the fabricated ESD cells with the RF-NMOS emulators are evaluated by the ESD tester in human body model (HBM). The positive-to- V_{DD} (PD-mode), positive-to- V_{SS} (PS-mode), negative-to- V_{DD} (ND-mode), and negative-to- V_{SS} (NS-mode) ESD robustness of each ESD cells are listed in Table I. The 0.5-, 1-, 1.5-, and 2-kV cells can sustain 0.75-, 1.5-, 2.25-,

TABLE I
DESIGN PARAMETERS AND MEASUREMENT RESULTS OF ESD CELLS

	0.5-kV Cell	1-kV Cell	1.5-kV Cell	2-kV Cell
Design Parameters	L₁	0.13 nH	0.13 nH	0.1 nH
	D_{P1}	8 μm / 0.6 μm	15 μm / 0.6 μm	13 μm / 0.6 μm
	D_{N1}	8 μm / 0.6 μm	15 μm / 0.6 μm	13 μm / 0.6 μm
	L₂	N/A	N/A	0.06 nH
	D_{P2}	N/A	N/A	10 μm / 0.6 μm
	D_{N2}	N/A	N/A	13 μm / 0.6 μm
	Cell Area	130 μm x 210 μm	130 μm x 210 μm	110 μm x 280 μm
Measurement Results	S₁₁ at 60 GHz	< -15 dB	< -25 dB	< -25dB
	S₂₂ at 60 GHz	~ 0.9 dB	~ 1.1 dB	~ 1.9 dB
	PD-Mode HBM	1 kV	2 kV	2.75 kV
	PS-Mode HBM	1 kV	1.75 kV	2.25 kV
	ND-Mode HBM	0.75 kV	1.5 kV	2.25 kV
	NS-Mode HBM	0.75 kV	1.5 kV	2.25 kV

and 2.5-kV HBM ESD tests, respectively. These ESD test results are even better than the original specification of these ESD cells. Besides, the power-rail ESD clamp circuit can sustain over 8-kV HBM ESD tests.

IV. CONCLUSION

The ESD cells for 60-GHz broadband RF applications are presented in this work. These ESD cells have reached the 50-Ω input/output matching. This ESD cell library reduces the design complexity for RF circuit designer and provides suitable ESD protection. Verified in a commercial sub-100nm CMOS process, the 0.5-, 1-, 1.5-, and 2-kV cells have about 0.9-, 1.1-, 1.9-, and 2.1-dB power loss, respectively. Besides, they can sustain 0.75-, 1.5-, 2.25-, and 2.5-kV HBM ESD tests, respectively. This ESD cell library is developed to support foundry's customers for them to easily apply ESD protection in the 60-GHz broadband RF circuits.

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